PATENT
Attorney Docket No. 203924

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Kodama et al.

Art Unit: 1711

Application No. 09/502,834

Examiner: D. Truong

Filed: February 11, 2000

For: POLYBENZAZOLE ARTICLE AND PRODUCTION METHOD THEREOF

PENDING CLAIMS AFTER AMENDMENTS MADE IN RESPONSE TO OFFICE ACTION DATED SEPTEMBER 6, 2002

1. A polybenzazole article superior in light resistance, which comprises a polybenzazole and a light-resisting agent that allows for a regular reflectance of the article of not more than 30% in not less than 30% of the wavelength region of from 450 nm to 700 nm, wherein the light-resisting agent is at least one member selected from the group consisting of aniline, *o*-phenylenediamine, *m*-phenylenediamine, *p*-phenylenediamine, *o*-aminophenol, *m*-aminophenol, *p*-aminophenol, 2-amino-4-nitrophenol, 2-aminophenol-4-sulfonamide, and 1,8-diaminonaphthalene.

2. The polybenzazole article of claim 1, wherein the light-resisting agent allows for a regular reflectance of the article of not more than 20% in not less than 10% of the wavelength region of from 450 nm to 700 nm.

3. The polybenzazole article of claim 1, which has a strength of not less than 35 g/d.

6. The polybenzazole article of claim 1, wherein the light-resisting agent is contained in a proportion of 0.01 to 20% by weight of the article.

CLAIM AMENDMENTS

1. (Currently Amended) A polybenzazole article superior in light resistance, which comprises a polybenzazole and a light-resisting agent that allows for a regular reflectance of the article of not more than 30% in not less than 30% of the wavelength region of from 450 nm to 700 nm, wherein the light-resisting agent is at least one member selected from the group consisting of ~~aniline, *o*-phenylenediamine,~~ *m*-phenylenediamine, *p*-phenylenediamine, *o*-aminophenol, ~~*m*-aminophenol, *p*-aminophenol,~~ 2-amino-4-nitrophenol, 2-aminophenol-4-sulfonamide, and 1,8-diaminonaphthalene.

2. (Original) The polybenzazole article of claim 1, wherein the light-resisting agent allows for a regular reflectance of the article of not more than 20% in not less than 10% of the wavelength region of from 450 nm to 700 nm.

3. (Original) The polybenzazole article of claim 1, which has a strength of not less than 35 g/d.

4. (Canceled)

5. (Canceled)

6. (Original) The polybenzazole article of claim 1, wherein the light-resisting agent is contained in a proportion of 0.01 to 20% by weight of the article.

7. (Canceled)

8. (Canceled)

9. (New) The polybenzazole article of claim 1, wherein the light-resisting agent comprises *m*-phenylenediamine and *p*-phenylenediamine in a weight ratio of about 1:1.

10. (New) The polybenzazole article of claim 1, wherein the light-resisting agent comprises *o*-aminophenol and *p*-phenylenediamine in a weight ratio of about 1:1.

11. (New) The polybenzazole article of claim 1, wherein the light-resisting agent comprises 2-amino-4-nitrophenol and *p*-phenylenediamine in a weight ratio of about 1:1.